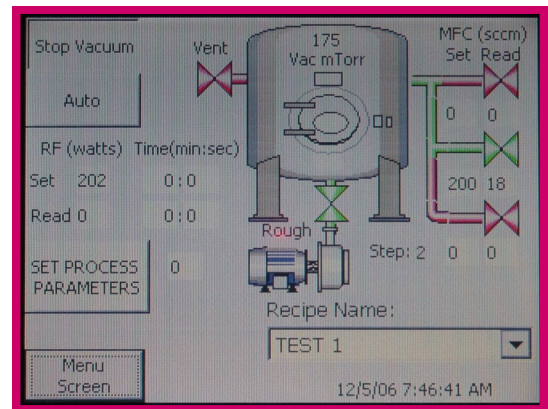


14" ALUMINUM REACTOR PLASMA SYSTEM SCE-AL-1414



Siemens "Touch Panel" Control



Vacuum and Process Control all in one.
Functions are clearly displayed



**ALUMINUM REACTOR
CHAMBER**
For industrial applications

**Immersing parts in low temperature plasma may be your final
cleaning solution !!**

Anatech's plasma systems are CFC and effluent free, operator and environmentally safe, easily operated.

No costly solvents or chemicals, No repeat rinses, No residues.
Throughput requirements form R&D to production

14" ALUMINUM REACTOR PLASMA SYSTEM

CONTROL SYSTEM:

- Siemens S7-200 Series Industrial Control Package (PLC)
- Low voltage 24 VDC Logic for I/O Devices
- LCD Touch Panel for operator interface to program

DIMENSIONS:

- Standard 19" Equipment rack
- 22.5"W x 25.5"D x 35.5"H
- Pump 30" L x 12" W x 18" H
- Shipping weight
- 600 lbs Crated weight

CONTROL SYSTEM OPTIONS:

- 3 gas channels - 1 standard
- Data logging
- Capacitance manometer
- Temperature sensor
- Throttle valve
- Nitrogen backfill
- Slow pump and particle reduction
- Process light (Optional)

VACUUM SYSTEM:

- 23.3 CFM Standard
- Pneumatic Vacuum Valve (PLC controlled)
- 6 feet of 1 1/2 "ID Vacuum line
- All interconnecting
- Mist filter

RF POWER SOURCE:

- 0-300 Watt, 13.56 MHz
- Forward and reflected power reading
- Automatic RF Tuning Network
- 3% Power regulation
- **Optional:** 600 or 1000 Watt 13.56 MHz supply
- Low frequency optional

VACUUM SYSTEM OPTIONS:

- Oxygen service
- Corrosive service
- Certain applications may require higher gas through put than standard. Pump needs to be sized accordingly.

FACILITY REQUIREMENTS:

- 115-VAC 15A 50/60-HZ
- 220-VAC optional
- 208/220 3P 30A Vacuum pump
- 60 PSI Clear dry air (CDA) for pneumatic vacuum valve

REACTOR CHAMBER 14" ALUMINUM:

- 14" Cube aluminum chamber
- Multiple shelves (2-Hot, 2-Ground)
- Front loading
- View port on front door
- Shelves can be configured in 4 different modes
- Downstream** - The samples can be placed on a neutral shelf surfaces for a gentle plasma effect
- Direct** - The samples can be placed on the power or ground shelves for maximum effect
- Directional** - Samples requiring anisotropic etching or cleaning are placed on a special powered shelf
- Special** - Where parallel configurations do not serve as optimum configuration, special electrode configurations can be supplied

CALL ANATECH USA TODAY TO DISCUSS YOUR APPLICATION

Anatech USA
1395 Greg Street
Suite 110
Sparks, NV 89431
775-657-8685